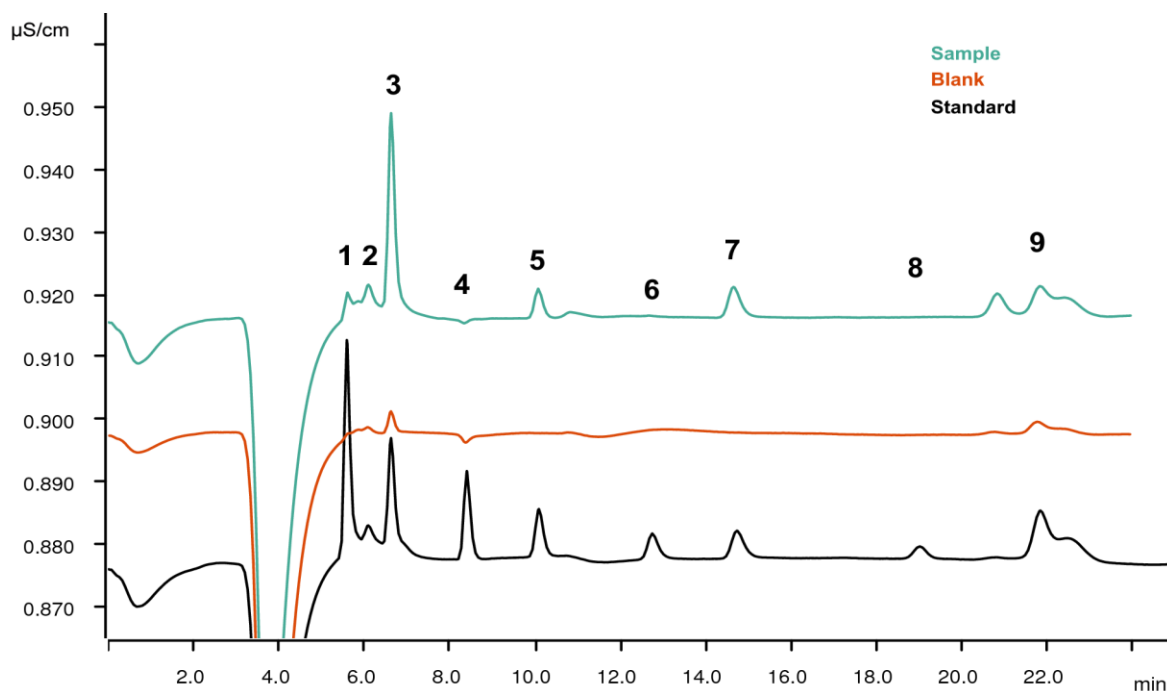


Anionic impurities in concentrated semiconductor grade ammonium hydroxide



Ultrapure chemicals are required to be applied in semiconductor industry. Ionic impurities may lead to compromised products. This application describes the determination of anionic impurities in semiconductor grade 28% ammonium hydroxide solution. To avoid matrix disturbances Inline Neutralization and Inline Preconcentration with Matrix Elimination needs to be applied.

Results

| Anion | Conc. [$\mu\text{g/L}$] | RSD [%, n = 6] | Anion | Conc. [$\mu\text{g/L}$] | RSD [%, n = 6] |
|------------|---------------------------|----------------|-------------|---------------------------|----------------|
| 1 Fluoride | 1.8 | 2.1 | 6 Bromide | n.d. | - |
| 2 Acetate | 11.1 | 13.7 | 7 Nitrate | 20.8 | 2.6 |
| 3 Formate | 56.7 | 2.9 | 8 Phosphate | n.d. | - |
| 4 Chloride | n.d. | - | 9 Sulfate | 7.9 | 5.5 |
| 5 Nitrite | 11.7 | 0.6 | | | |

Standard in graph: acetate, formate 8 $\mu\text{g/L}$ each, all others 4 $\mu\text{g/L}$ each

